## **AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1-7 (Canceled).

8. (New) A method of manufacturing a silicon wafer, the method comprising: polishing side faces of a silicon block used for manufacturing the silicon wafer;

slicing the silicon block.

and

- 9. (New) The method of claim 8, wherein the polished side faces of the silicon block have a surface roughness Ry of 8µm or less.
- 10. (New) A method of manufacturing a silicon inclusive wafer, the method comprising:

polishing side faces of a block comprising silicon, which is used for manufacturing the silicon inclusive wafer; and slicing the block.

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11. (New) The method of claim 10, wherein at least one polished side face of the block has a surface roughness Ry of  $8\mu m$  or less.